

Standard Crystal-TRIM

Tutorials 2025

The following shows some applications of the code with inputs and outputs appearing on the computer monitor.

The commands (on the command line) and the data to be given by the user are shown in bold face. The commands are in the style for the MSDOS version. If the linux version is used the commands must begin with ./

In the following examples the computing time is mostly less than 10 minutes (valid for calculations on both linux and MSDOS systems). The input and output data files can be found in the corresponding folders.

The diagrams shown below were generated using Origin Lab®.

Example A:

**100 keV B into (100) Si, 10^{14} cm⁻², 0° tilt, 0° rotation
15 Å SiO₂ amorphous top layer**

Calculation without considering damage accumulation since this effect is not relevant here.

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

Crystal-TRIM
developed by Matthias Posselt
(C) Since 1991 by
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Input Dialog

File names consist of a variable first part
and a constant second part.
Name of the first part?(exactly 4 ASCII characters!)

b1ha

substrate:
single-crystalline Si (1)?

single-crystalline Ge (2)?
 diamond (3)?
1
 Ion
 Energy in keV?
100
 Orientation of the substrate surface (e.g. 1 0 0) ?

 Insert a space between the integers!
 Please note: Only (100),(110) and (111) surfaces can
 be considered!
1 0 0
 Tilt angle theta0 in deg.?
0
 Rotation angle phi0 in deg.)?
0
 Name of the file which contains the parameters
 for ZBL electronic stopping?
 scoef1.dat - original ZBL 1985 (1)
 scoef2.dat - 1989 (2)
 scoef1.dat = default in previous Crystal-TRIM applications
1
 Atomic (1) or molecular (2) ion?
1
 Atomic number?
5
 Mass: most abundant isotope (1), another (2)
1
 clambda is 1.010

 use this standard value (yes 1, no 2)?
1
 Cel and Cel110 different from 1? (no 1, yes 2)
1
 Number of ion histories to be simulated?
10000
 Use of an efficient splitting procedure
 to improve the statistical precision (no 1, yes 2)?
 Splitting is particularly recommended in cases
 where long channeling tails are expected.
1
 Number of amorphous layers on top of
 the single-crystalline substrate (Max.:10):
1
 Layer 1 --Thickness (Angstrom)?
 (total thickness of layers must not exceed 1e+05 A)
15
 Density (g/cm-3)?
2.24
 SiO2 (1) or another layer (2)?
1
 Crystalline substrate:
 Temperature different from RT (300K)? (no 1, yes 2)
1
 Consideration of damage accumulation
 (phenomenological models)? (no 1, yes 2)

1

Width of the intervals in the histograms (A)?
Maximum number of depth intervals is 400

100

Final energy in the simulation of
the motion of the ions?

Estimation:

E(keV)	Range(A)
0.500E+00	0.273E+02

Final energy in the simulation of
the motion of the ions (keV)?

0.5

writing to input file b1ha.DAT

The input data files b1ha.IN and b1ha.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < b1ha.IN

```
start in981
reading from input file    b1ha.DAT
input file closed
end in981
start sec971
end sec971
start pro981
status of calculation in %    particle histories
10                    1000
20                    1999
30                    2998
40                    3997
50                    4996
60                    5995
70                    6994
80                    7993
90                    8992
100                   9991
end pro981
start out981
writing to output file    b1ha.OUT
writing to output file    b1ha.1D1
output file b1ha.1D1       closed
output file b1ha.OUT       closed
end out981
```

The output data files b1ha.OUT, b1ha.1D1 and b1ha.ST have been written. Only b1ha.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

program prof1z
input data file?
(not more than 12 ASCII characters)

b1ha.1D1

output data file?
(not more than 14 ASCII characters)

b1harange.dat

options:

iopt

- 1 range profile
- 2 nuclear energy deposition
- 3 electronic energy deposition
- 4 damage concentration (only valid in c-Si)
- 5 damage probability (only valid in c-Si)

iopt?

1

backscattering yield (see file "name.OUT")?

0.

dose (cm**(-2))?

1.e14

reading from input file b1ha.1D1
input file b1ha.1D1 closed
writing to output file b1harange.dat
output file b1harange.dat closed

Example B:

**100 keV B into (100) Si, 10^{14} cm^{-2} , 7° tilt, 22.5° rotation
15 Å SiO₂ amorphous top layer**

Calculation without considering damage accumulation since this effect is not relevant here.

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

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Input Dialog

File names consist of a variable first part

and a constant second part.

Name of the first part?(exactly 4 ASCII characters!)

b1hb

substrate:

single-crystalline Si (1)?

single-crystalline Ge (2)?

diamond (3)?

1

Ion

Energy in keV?

100

Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!

Please note: Only (100),(110) and (111) surfaces can be considered!

1 0 0

Tilt angle theta0 in deg.?

7

Rotation angle phi0 in deg.)?

22.5

Name of the file which contains the parameters for ZBL electronic stopping?

scoef1.dat - original ZBL 1985 (1)

scoef2.dat - 1989 (2)

scoef1.dat = default in previous Crystal-TRIM applications

1

Atomic (1) or molecular (2) ion?

1

Atomic number?

5

Mass: most abundant isotope (1), another (2)

1

clambda is 1.010

use this standard value (yes 1, no 2)?

1

Cel and Cel110 different from 1? (no 1, yes 2)

1

Number of ion histories to be simulated?

10000

Use of an efficient splitting procedure to improve the statistical precision (no 1, yes 2)?
Splitting is particularly recommended in cases where long channeling tails are expected.

2

Measure of the statistical precision of simulation results: ISIGDEPTH?

20

Number of amorphous layers on top of the single-crystalline substrate (Max.:10):

1

Layer 1 --Thickness (Angstrom)?

(total thickness of layers must not exceed 1e+05 Å)

15

Density (g/cm-3)?

2.24

SiO₂ (1) or another layer (2)?

1

Crystalline substrate:

Temperature different from RT (300K)? (no 1, yes 2)

1

Consideration of damage accumulation
(phenomenological models)? (no 1, yes 2)

1

Width of the intervals in the histograms (A)?

Maximum number of depth intervals is 400

100

Final energy in the simulation of
the motion of the ions?

Estimation:

E(keV) Range(A)

0.500E+00 0.273E+02

Final energy in the simulation of
the motion of the ions (keV)?

0.5

writing to input file b1hb.DAT

The input data files b1hb.IN and b1hb.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < b1hb.IN

start in981

reading from input file b1hb.DAT

input file closed

end in981

start sec971

end sec971

start pro981

status of calculation in % particle histories

10 1000

20 1999

30 2998

40 3997

50 4996

60 5995

70 6994

80 7993

90 8992

100 9991

end pro981

start out981

writing to output file b1hb.OUT

writing to output file b1hb.1D1

output file b1hb.1D1 closed

output file b1hb.OUT closed

end out981

The output data files b1hb.OUT, b1hb.1D1 and b1hb.ST have been written. Only b1hb.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

program prof1z
input data file?
(not more than 12 ASCII characters)

b1hb.1D1

output data file?
(not more than 14 ASCII characters)

b1hbrange.dat

options:

iopt

- 1 range profile
- 2 nuclear energy deposition
- 3 electronic energy deposition
- 4 damage concentration (only valid in c-Si)
- 5 damage probability (only valid in c-Si)

iopt?

1

backscattering yield (see file "name.OUT")?

0.

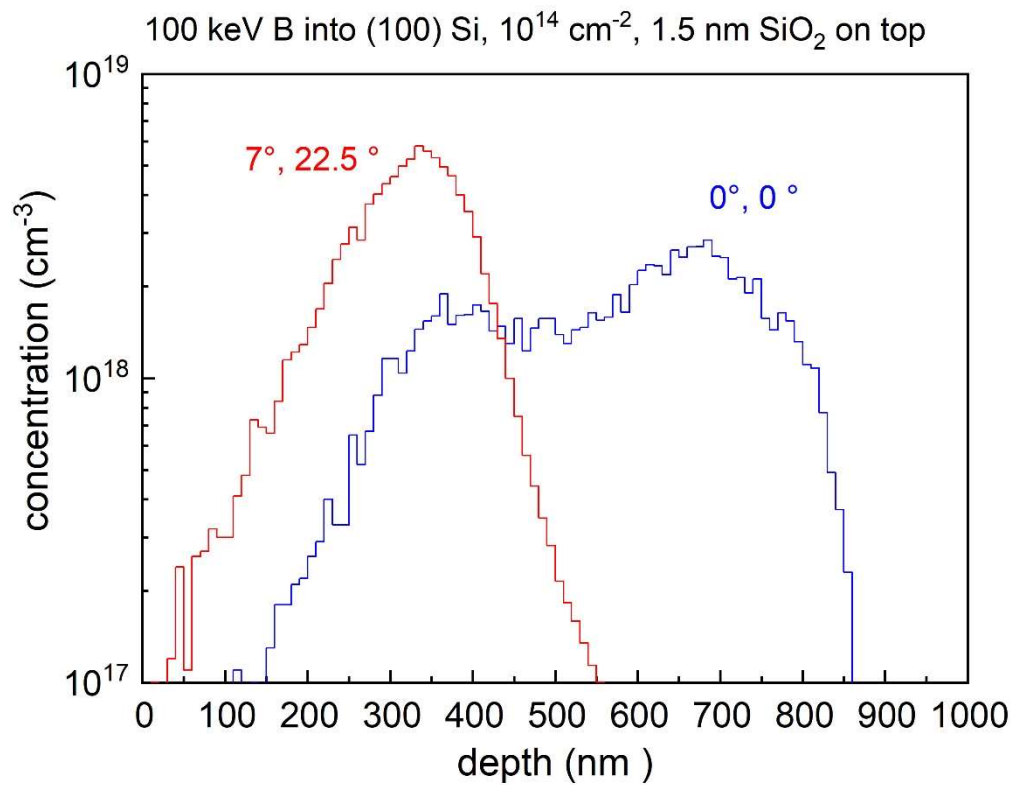
dose (cm⁻²)?

1.e14

reading from input file b1hb.1D1
input file b1hb.1D1 closed
writing to output file b1hbrange.dat
output file b1hbrange.dat closed

Graphical representation of B depth profiles for Examples A and B

The following diagrams show the B depth profiles b1harange.dat and b1hbrange.dat. Note the logarithmic scale on the ordinate, which is relevant for implantation of electrical dopants in order to determine the location of the p-n junction. The logarithmic scale shows the so-called channeling tail in the case of 7° tilt implantation. If the Si substrate were amorphous this tail would not exist and after the peak the decrease would be very steep.



The data shown were calculated using MSDOS executables on a certain Windows system. On various systems and processors, the individual numbers may be not identical. However, all these results are statistically not different. This holds for calculations under MSDOS and Linux.

Example C

**100 keV P into (100) Si, 10^{15} cm^{-2} , 0° tilt, 0° rotation
15 Å SiO₂ amorphous top layer**

Calculation without considering damage accumulation.

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

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Input Dialog

File names consist of a variable first part
and a constant second part.
Name of the first part?(exactly 4 ASCII characters!)

p1ha

substrate:
single-crystalline Si (1)?
single-crystalline Ge (2)?
diamond (3)?

1

Ion
Energy in keV?

100

Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!

Please note: Only (100),(110) and (111) surfaces can
be considered!

1 0 0

Tilt angle theta0 in deg.?

0

Rotation angle phi0 in deg.)?

0

Name of the file which contains the parameters
for ZBL electronic stopping?

scoef1.dat - original ZBL 1985 (1)

scoef2.dat - 1989 (2)

scoef1.dat = default in previous Crystal-TRIM applications

1

Atomic (1) or molecular (2) ion?

1

Atomic number?

15

Mass: most abundant isotope (1), another (2)

1

clambda is 1.000

use this standard value (yes 1, no 2)?

1

Cel and Cel110 different from 1? (no 1, yes 2)

2

Cel110?

0.97

Cel?

1.45

Number of ion histories to be simulated?

10000

Use of an efficient splitting procedure
to improve the statistical precision (no 1, yes 2)?
Splitting is particularly recommended in cases
where long channeling tails are expected.

1

Number of amorphous layers on top of
the single-crystalline substrate (Max.:10):

1

Layer 1 --Thickness (Angstrom)?
(total thickness of layers must not exceed 1e+05 A)

15

Density (g/cm-3)?

2.24

SiO2 (1) or another layer (2)?

1

Crystalline substrate:
Temperature different from RT (300K)? (no 1, yes 2)

1

Consideration of damage accumulation
(phenomenological models)? (no 1, yes 2)

1

Width of the intervals in the histograms (A)?
Maximum number of depth intervals is 400

50

Final energy in the simulation of
the motion of the ions?
Estimation:
E(keV) Range(A)
0.300E+00 0.127E+02
Final energy in the simulation of
the motion of the ions (keV)?

0.3

writing to input file p1ha.DAT

The input data files p1ha.IN and p1ha.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < p1ha.IN

```
start in981
reading from input file   p1ha.DAT
input file closed
end in981
start sec971
end sec971
start pro981
status of calculation in %  particle histories
    10          1000
    20          1999
    30          2998
    40          3997
    50          4996
    60          5995
    70          6994
    80          7993
    90          8992
   100          9991
end pro981
start out981
writing to output file   p1ha.OUT
writing to output file   p1ha.1D1
output file p1ha.1D1      closed
output file p1ha.OUT      closed
end out981
```

The output data files p1ha.OUT, p1ha.1D1 and p1ha.ST have been written. Only p1ha.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

```
program prof1z
input data file?
(not more than 12 ASCII characters)
```

p1ha.1D1

```
output data file?
(not more than 14 ASCII characters)
```

p1harange.dat

```
options:
iopt
1    range profile
2    nuclear energy deposition
3    electronic energy deposition
4    damage concentration (only valid in c-Si)
5    damage probability (only valid in c-Si)    iopt?
```

1

```
backscattering yield (see file "name.OUT")?
```

0.

dose (cm⁻²)?

1.e15

reading from input file p1ha.1D1

input file p1ha.1D1 closed

writing to output file p1harange.dat

output file p1harange.dat closed

Example D

**100 keV P into (100) Si, 10¹⁵ cm⁻², 7° tilt, 22.5° rotation
15 Å SiO₂ amorphous top layer**

Calculation without considering damage accumulation.

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

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Input Dialog

File names consist of a variable first part
and a constant second part.

Name of the first part?(exactly 4 ASCII characters!)

p1hb

substrate:

single-crystalline Si (1)?

single-crystalline Ge (2)?

diamond (3)?

1

Ion

Energy in keV?

100

Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!

Please note: Only (100),(110) and (111) surfaces can
be considered!

1 0 0

Tilt angle theta0 in deg.?

7

Rotation angle phi0 in deg.)?

22.5
 Name of the file which contains the parameters
 for ZBL electronic stopping?
 scoef1.dat - original ZBL 1985 (1)
 scoef2.dat - 1989 (2)
 scoef1.dat = default in previous Crystal-TRIM applications

1
 Atomic (1) or molecular (2) ion?

1
 Atomic number?

15
 Mass: most abundant isotope (1), another (2)

1
 clambda is 1.000

use this standard value (yes 1, no 2)?

1
 Cel and Cel110 different from 1? (no 1, yes 2)

2
 Cel110?

0.97
 Cel?

1.45
 Number of ion histories to be simulated?

10000
 Use of an efficient splitting procedure
 to improve the statistical precision (no 1, yes 2)?
 Splitting is particularly recommended in cases
 where long channeling tails are expected.

2
 Measure of the statistical precision of simulation
 results: ISIGDEPTH?

20
 Number of amorphous layers on top of
 the single-crystalline substrate (Max.:10):

1
 Layer 1 --Thickness (Angstrom)?
 (total thickness of layers must not exceed 1e+05 A)

15
 Density (g/cm-3)?

2.24
 SiO2 (1) or another layer (2)?

1
 Crystalline substrate:
 Temperature different from RT (300K)? (no 1, yes 2)

1
 Consideration of damage accumulation
 (phenomenological models)? (no 1, yes 2)

1
 Width of the intervals in the histograms (A)?
 Maximum number of depth intervals is 400

50
 Final energy in the simulation of
 the motion of the ions?
 Estimation:

E(keV) Range(A)
0.300E+00 0.127E+02
Final energy in the simulation of
the motion of the ions (keV)?

0.3

writing to input file p1hb.DAT

The input data files p1hb.IN and p1hb.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < p1hb.IN

```
start in981
reading from input file    p1hb.DAT
input file closed
end in981
start sec971
end sec971
start pro981
status of calculation in %    particle histories
10                    1000
20                    1999
30                    2998
40                    3997
50                    4996
60                    5995
70                    6994
80                    7993
90                    8992
100                   9991
end pro981
start out981
writing to output file    p1hb.OUT
writing to output file    p1hb.1D1
output file    p1hb.1D1            closed
output file    p1hb.OUT           closed
end out981
```

The output data files p1hb.OUT, p1hb.1D1 and p1hb.ST have been written. Only p1hb.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

program prof1z
input data file?
(not more than 12 ASCII characters)

p1hb.1D1

output data file?
(not more than 14 ASCII characters)

p1hbrange.dat

options:

iopt

- 1 range profile
- 2 nuclear energy deposition
- 3 electronic energy deposition
- 4 damage concentration (only valid in c-Si)
- 5 damage probability (only valid in c-Si) iopt?

1

backscattering yield (see file "name.OUT")?

0.

dose (cm⁻²)?

1.e15

reading from input file p1hb.1D1

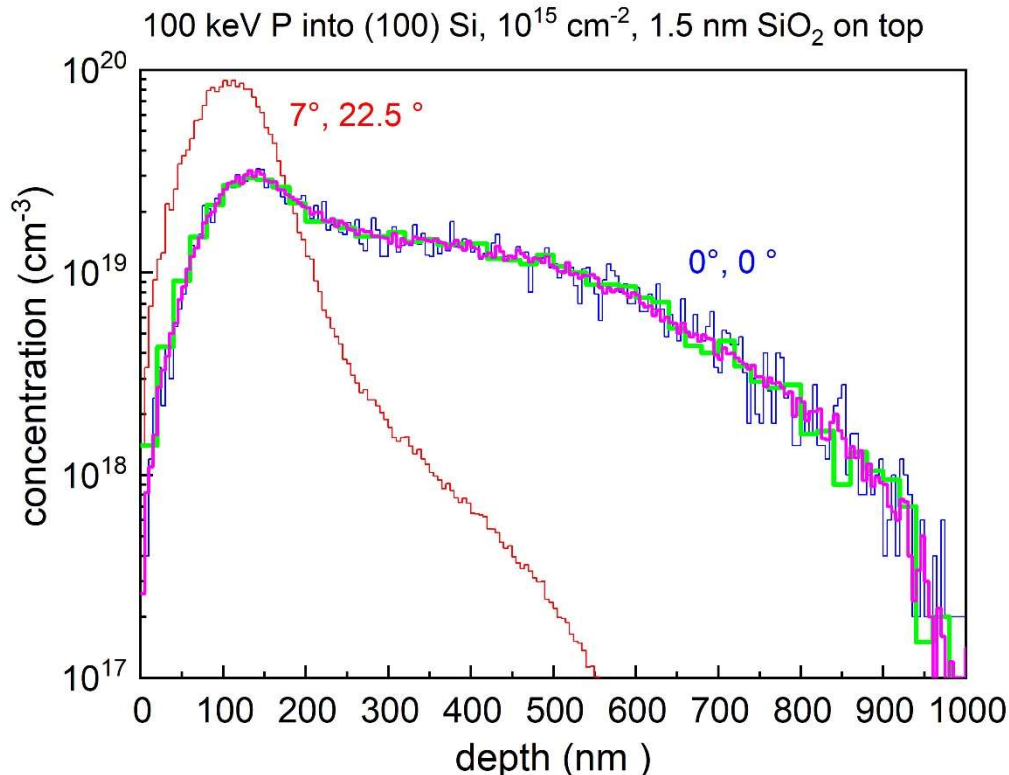
input file p1hb.1D1 closed

writing to output file p1hbrange.dat

output file p1hbrange.dat closed

Graphical representation of P depth profiles for Examples C and D

The following diagram shows the P depth profiles p1harange.dat (blue) and p1hbrange.dat (red). Note that in the case of 0° implantation the interval width is too small to give a "good statistical shape" of the profile. Improvements: Either use a larger interval width or a more projectile (ion) histories (more than 10000). For comparison, the green histogram shows a depth profile for 0° implantation with an interval width of 200 Å instead of 50 Å. The magenta histogram shows results of simulation with 100000 projectile histories instead of 10000.



Example E

**100 keV P into (100) Si, 10^{15} cm^{-2} , 0° tilt, 0° rotation
15 Å SiO₂ amorphous top layer**

Calculation with considering damage accumulation.

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

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Input Dialog

File names consist of a variable first part
and a constant second part.
Name of the first part?(exactly 4 ASCII characters!)

p1hc

substrate:
single-crystalline Si (1)?
single-crystalline Ge (2)?
diamond (3)?

1

Ion
Energy in keV?

100

Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!

Please note: Only (100),(110) and (111) surfaces can
be considered!

1 0 0

Tilt angle theta0 in deg.?

0

Rotation angle phi0 in deg.)?

0

Name of the file which contains the parameters
for ZBL electronic stopping?

scoef1.dat - original ZBL 1985 (1)

scoef2.dat - 1989 (2)

scoef1.dat = default in previous Crystal-TRIM applications

1

Atomic (1) or molecular (2) ion?

1

Atomic number?

15

Mass: most abundant isotope (1), another (2)

1

clambda is 1.000

use this standard value (yes 1, no 2)?

1

Cel and Cel110 different from 1? (no 1, yes 2)

2

Cel110?

0.97

Cel?

1.45

Number of ion histories to be simulated?

10000

Use of an efficient splitting procedure
to improve the statistical precision (no 1, yes 2)?
Splitting is particularly recommended in cases
where long channeling tails are expected.

2

Measure of the statistical precision of simulation
results: ISIGDEPTH?

20

Number of amorphous layers on top of
the single-crystalline substrate (Max.:10):

1

Layer 1 --Thickness (Angstrom)?
(total thickness of layers must not exceed 1e+05 A)

15

Density (g/cm-3)?

2.24

SiO2 (1) or another layer (2)?

1

Crystalline substrate:
Temperature different from RT (300K)? (no 1, yes 2)

1

Consideration of damage accumulation
(phenomenological models)? (no 1, yes 2)

2

Model number (1,2,3,4,5,6)?

6

cacc? (between 0. and 1.)?

0.2

ccrit (between 0. and 1.)?

0.1

Dose (cm**(-2)) ?

1.e15

Does a predamage exist? (no 1, yes 2)

1

Width of the intervals in the histograms (A)?
Maximum number of depth intervals is 400

50

Final energy in the simulation of

the motion of the ions?

Estimation:

E(keV)	Range(A)
0.300E+00	0.127E+02

Final energy in the simulation of
the motion of the ions (keV)?

0.3

writing to input file p1hc.DAT

The input data files p1hc.IN and p1hc.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < p1hc.IN

```
start in981
reading from input file    p1hc.DAT
input file closed
end in981
start sec971
end sec971
start pro981
status of calculation in %    particle histories
10                    1000
20                    1999
30                    2998
40                    3997
50                    4996
60                    5995
70                    6995
80                    7993
90                    8993
100                   9991
end pro981
start out981
writing to output file    p1hc.OUT
writing to output file    p1hc.1D1
output file p1hc.1D1       closed
output file p1hc.OUT       closed
end out981
```

The output data files p1hc.OUT, p1hc.1D1 and p1hc.ST have been written. Only p1hc.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

```
program prof1z
input data file?
(not more than 12 ASCII characters)
```

p1hc.1D1

output data file?
(not more than 14 ASCII characters)

p1hcrange.dat

options:

iopt

- 1 range profile
- 2 nuclear energy deposition
- 3 electronic energy deposition
- 4 damage concentration (only valid in c-Si)
- 5 damage probability (only valid in c-Si)

iopt?

1

backscattering yield (see file "name.OUT")?

0.

dose (cm^{**(-2)})?

1.e15

reading from input file p1hc.1D1
input file p1hc.1D1 closed
writing to output file p1hcrange.dat
output file p1hcrange.dat closed

Additionally: calculation of the damage (or amorphization) probability:

prof1z.exe

program prof1z
input data file?
(not more than 12 ASCII characters)

p1hc.1D1

output data file?
(not more than 14 ASCII characters)

p1hcopt5.dat

options:

iopt

- 1 range profile
- 2 nuclear energy deposition
- 3 electronic energy deposition
- 4 damage concentration (only valid in c-Si)
- 5 damage probability (only valid in c-Si)

iopt?

5

backscattering yield (see file "name.OUT")?

0.

atomic density of the single-crystalline substrate
in Angstrom^{**(-3)} (see ARHO in "name.OUT")?

0.05

dose (cm^{**(-2)})?

1.e15

reading from input file p1hc.1D1
input file p1hc.1D1 closed
writing to output file p1hcopt5.dat
output file p1hcopt5.dat closed

Note that the 0.05 is the *approximate* value of the atomic density of Si.

Example F

**100 keV P into (100) Si, 10^{15} cm^{-2} , 7° tilt, 22.5° rotation
15 Å SiO₂ amorphous top layer**

Calculation with considering damage accumulation.

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

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Input Dialog

File names consist of a variable first part
and a constant second part.

Name of the first part?(exactly 4 ASCII characters!)

p1hd

substrate:

single-crystalline Si (1)?

single-crystalline Ge (2)?

diamond (3)?

1

Ion

Energy in keV?

100

Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!

Please note: Only (100),(110) and (111) surfaces can
be considered!

1 0 0

Tilt angle theta0 in deg.?

7

Rotation angle phi0 in deg.)?

22.5

Name of the file which contains the parameters
for ZBL electronic stopping?

scoef1.dat - original ZBL 1985 (1)

scoef2.dat - 1989 (2)

scoef1.dat = default in previous Crystal-TRIM applications

1

Atomic (1) or molecular (2) ion?

1

Atomic number?

15

Mass: most abundant isotope (1), another (2)

1

clambda is 1.000

use this standard value (yes 1, no 2)?

1

Cel and Cel110 different from 1? (no 1, yes 2)

2

Cel110?

0.97

Cel?

1.45

Number of ion histories to be simulated?

10000

Use of an efficient splitting procedure
to improve the statistical precision (no 1, yes 2)?
Splitting is particularly recommended in cases
where long channeling tails are expected.

2

Measure of the statistical precision of simulation
results: ISIGDEPTH?

20

Number of amorphous layers on top of
the single-crystalline substrate (Max.:10):

1

Layer 1 --Thickness (Angstrom)?
(total thickness of layers must not exceed 1e+05 A)

15

Density (g/cm-3)?

2.24

SiO2 (1) or another layer (2)?

1

Crystalline substrate:
Temperature different from RT (300K)? (no 1, yes 2)

1

Consideration of damage accumulation
(phenomenological models)? (no 1, yes 2)

2

Model number (1,2,3,4,5,6)?

6

cacc? (between 0. and 1.)?

0.2

ccrit (between 0. and 1.)?

0.1

Dose (cm**(-2)) ?

1.e15

Does a predamage exist? (no 1, yes 2)

1

Width of the intervals in the histograms (A)?
Maximum number of depth intervals is 400

50

Final energy in the simulation of

the motion of the ions?

Estimation:

E(keV) Range(A)

0.300E+00 0.127E+02

Final energy in the simulation of
the motion of the ions (keV)?

0.3

writing to input file p1hd.DAT

The input data files p1hd.IN and p1hd.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < p1hd.IN

```
start in981
reading from input file    p1hd.DAT
input file closed
end in981
start sec971
end sec971
start pro981
status of calculation in %    particle histories
10                    1000
20                    1999
30                    2998
40                    3997
50                    4996
60                    5995
70                    6994
80                    7994
90                    8992
100                   9992
end pro981
start out981
writing to output file    p1hd.OUT
writing to output file    p1hd.1D1
output file    p1hd.1D1        closed
output file    p1hd.OUT        closed
end out981
```

The output data files p1hd.OUT, p1hd.1D1 and p1hd.ST have been written. Only p1hd.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

program prof1z
input data file?
(not more than 12 ASCII characters)

p1hd.1D1

output data file?
(not more than 14 ASCII characters)

p1hdrange.dat

options:
iopt
1 range profile
2 nuclear energy deposition
3 electronic energy deposition
4 damage concentration (only valid in c-Si)
5 damage probability (only valid in c-Si)

iopt?

1
backscattering yield (see file "name.OUT")?

0.
dose (cm**(-2))?

1.e15
reading from input file p1hd.1D1
input file p1hd.1D1 closed
writing to output file p1hdrange.dat
output file p1hdrange.dat closed

Additionally: calculation of the damage (or amorphization) probability:

prof1z.exe

program prof1z
input data file?
(not more than 12 ASCII characters)

p1hd.1D1

output data file?
(not more than 14 ASCII characters)

p1hdopt5.dat

options:
iopt
1 range profile
2 nuclear energy deposition
3 electronic energy deposition
4 damage concentration (only valid in c-Si)
5 damage probability (only valid in c-Si)

iopt?

5
backscattering yield (see file "name.OUT")?

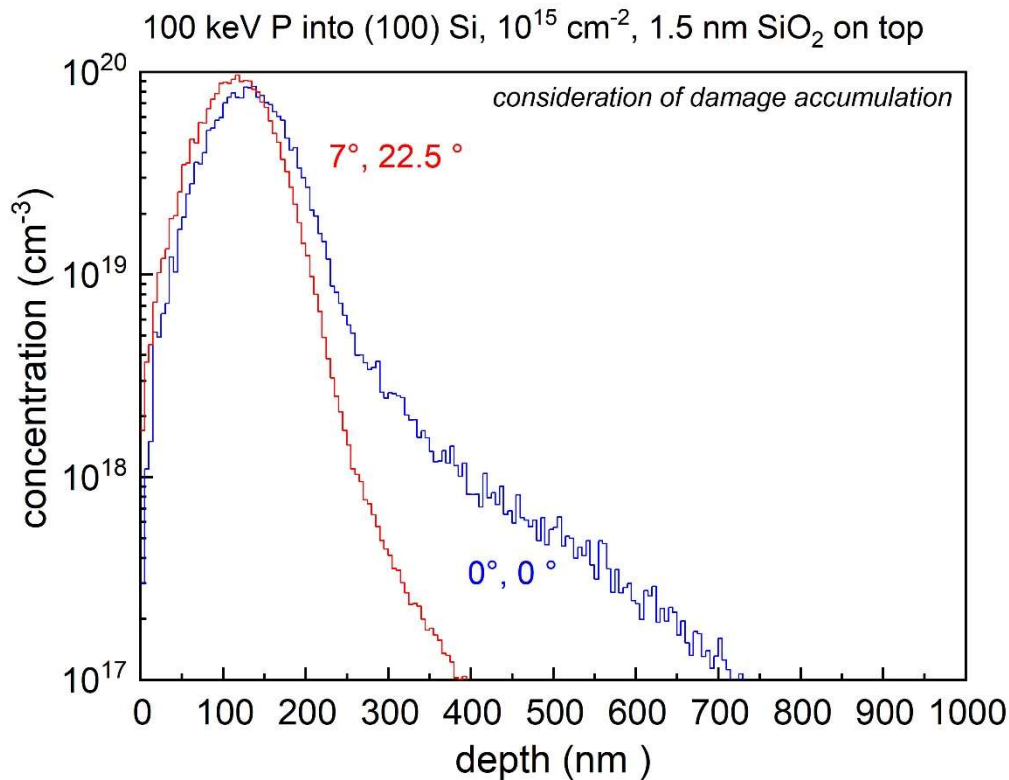
0.
atomic density of the single-crystalline substrate
in Angstroem**-3 (see ARHO in "name.OUT")?

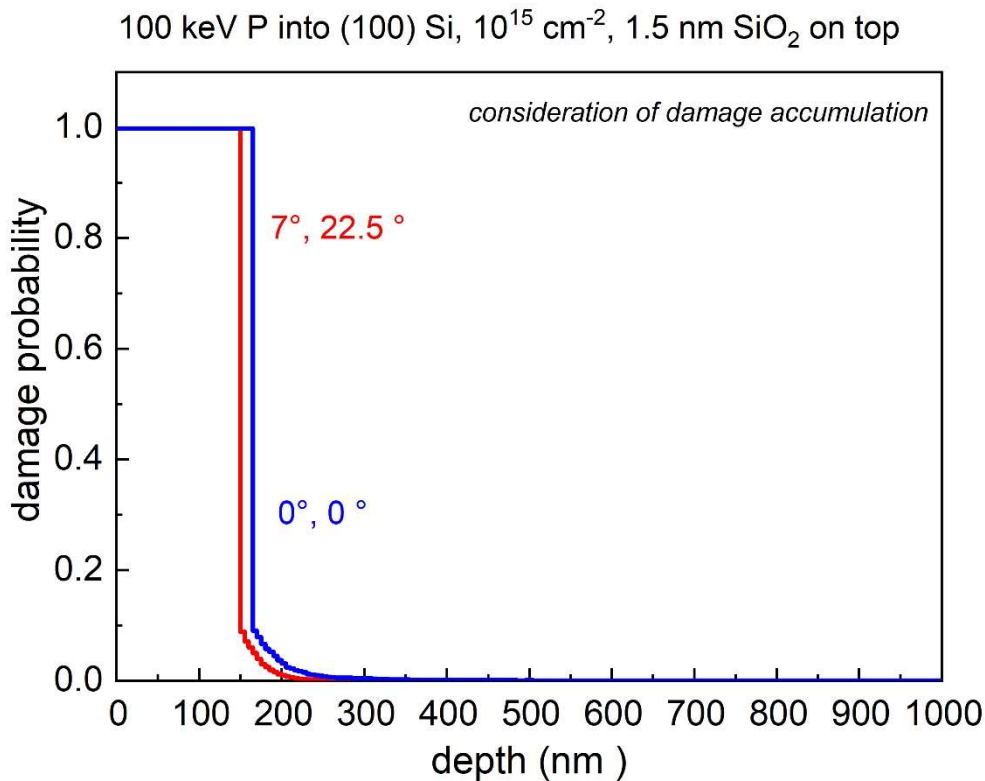
0.05
dose (cm**(-2))?

1.e15
reading from input file p1hd.1D1
input file p1hd.1D1 closed
writing to output file p1hdopt5.dat
output file p1hdopt5.dat closed

Graphical representation of P depth profiles for Examples E and F

The first diagram shows the P depth profiles p1hcrange.dat and p1hdrange.dat. The diagram differs considerably from that for p1harange.dat and p1hbrange.dat (Examples C and D), which demonstrates that damage accumulation cannot be neglected if the dose is 10^{15} cm^{-2} . The second diagram depicts the depth profile of the damage (or amorphization) probability (p1hcpt5.dat and p1hdopt5.dat). Probability 1 means amorphization. In this manner the depth of the amorphized layer can be determined.





Example G

75 keV ^{116}Sn into (100) diamond, 10^{10} cm^{-2} , 0° tilt, 0° rotation

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

Crystal-TRIM
developed by Matthias Posselt
(C) Since 1991 by
Matthias Posselt
Helmholtz-Zentrum Dresden-Rossendorf
Institute of Ion Beam Physics and
Materials Research
Bautzner Landstr. 400
D-01328 Dresden, Germany

Input Dialog

File names consist of a variable first part
and a constant second part.
Name of the first part?(exactly 4 ASCII characters!)

s75a

substrate:
single-crystalline Si (1)?

single-crystalline Ge (2)?
diamond (3)?

3
Ion
Energy in keV?

75
Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!
Please note: Only (100),(110) and (111) surfaces can
be considered!

1 0 0
Tilt angle theta0 in deg.?

0
Rotation angle phi0 in deg.)?

0
Name of the file which contains the parameters
for ZBL electronic stopping?
scoef1.dat - original ZBL 1985 (1)
scoef2.dat - 1989 (2)
scoef1.dat = default in previous Crystal-TRIM applications

1
Atomic (1) or molecular (2) ion?

1
Atomic number?

50
Mass: most abundant isotope (1), another (2)

2
Mass number?

116
clambda is 0.900

use this standard value (yes 1, no 2)?

1
Cel and Cel110 different from 1? (no 1, yes 2)

1
Number of ion histories to be simulated?

10000
Use of an efficient splitting procedure
to improve the statistical precision (no 1, yes 2)?
Splitting is particularly recommended in cases
where long channeling tails are expected.

1
Number of amorphous layers on top of
the single-crystalline substrate (Max.:10):

0
Crystalline substrate:
Temperature different from RT (300K)? (no 1, yes 2)

1
Consideration of damage accumulation
(phenomenological models)? (no 1, yes 2)

1
Width of the intervals in the histograms (A)?
Maximum number of depth intervals is 400

25
Final energy in the simulation of

the motion of the ions?

Estimation:

E(keV) Range(A)

0.375E+00 0.657E+01

Final energy in the simulation of
the motion of the ions (keV)?

0.375

writing to input file s75a.DAT

The input data files s75a.IN and s75a.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < s75a.IN

```
start in981
reading from input file    s75a.DAT
input file closed
end in981
start sec971
end sec971
start pro981
status of calculation in %    particle histories
10                    1000
20                    1999
30                    2998
40                    3997
50                    4996
60                    5995
70                    6994
80                    7993
90                    8992
100                   9991
end pro981
start out981
writing to output file    s75a.OUT
writing to output file    s75a.1D1
output file s75a.1D1      closed
output file s75a.OUT      closed
end out981
```

The output data files s75a.OUT, s75a.1D1 and s75a.ST have been written. Only s75a.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

```
program prof1z
input data file?
(not more than 12 ASCII characters)
```

s75a.1D1

```

        output data file?
        (not more than 14 ASCII characters)
s75arange.dat
        options:
        iopt
        1      range profile
        2      nuclear energy deposition
        3      electronic energy deposition
        4      damage concentration (only valid in c-Si)
        5      damage probability (only valid in c-Si)
        iopt?
1
        backscattering yield (see file "name.OUT")?
0.
        dose (cm**(-2))?
1.e10
        reading from input file   s75a.1D1
        input file  s75a.1D1      closed
        writing to output file   s75arange.dat
        output file s75arange.dat closed

```

Additionally: calculation of the “damage concentration”, i.e. of the concentration of the ballistically displaced atoms (formation of vacancies and self-interstitials):

```

        program prof1z
        input data file?
        (not more than 12 ASCII characters)
s75a.1D1
        output data file?
        (not more than 14 ASCII characters)
s75aopt4.dat
        options:
        iopt
        1      range profile
        2      nuclear energy deposition
        3      electronic energy deposition
        4      damage concentration (only valid in c-Si)
        5      damage probability (only valid in c-Si)
        iopt?
4
        backscattering yield (see file "name.OUT")?
0.
        dose (cm**(-2))?
1.e10
        reading from input file   s75a.1D1
        input file  s75a.1D1      closed
        writing to output file   s75aopt4.dat
        output file s75aopt4.dat closed

```

Example H

75 keV ^{116}Sn into (100) diamond, 10^{10} cm^{-2} , 7° tilt, 22.5° rotation

Step 1: Input dialog using the program xtru04.exe

xtru04.exe

Crystal-TRIM
developed by Matthias Posselt
(C) Since 1991 by
Matthias Posselt
Helmholtz-Zentrum Dresden-Rossendorf
Institute of Ion Beam Physics and
Materials Research
Bautzner Landstr. 400
D-01328 Dresden, Germany

Input Dialog

File names consist of a variable first part
and a constant second part.
Name of the first part?(exactly 4 ASCII characters!)

s75b

substrate:
single-crystalline Si (1)?
single-crystalline Ge (2)?
diamond (3)?

3

Ion
Energy in keV?

75

Orientation of the substrate surface (e.g. 1 0 0) ?

Insert a space between the integers!

Please note: Only (100),(110) and (111) surfaces can
be considered!

1 0 0

Tilt angle theta0 in deg.?

7

Rotation angle phi0 in deg.)?

22.5

Name of the file which contains the parameters
for ZBL electronic stopping?
scoef1.dat - original ZBL 1985 (1)
scoef2.dat - 1989 (2)
scoef1.dat = default in previous Crystal-TRIM applications

1

Atomic (1) or molecular (2) ion?

1

Atomic number?

50
 Mass: most abundant isotope (1), another (2)
 2
 Mass number?
 116
 clambda is 0.900

 use this standard value (yes 1, no 2)?
 1
 Cel and Cel110 different from 1? (no 1, yes 2)
 1
 Number of ion histories to be simulated?
 10000
 Use of an efficient splitting procedure
 to improve the statistical precision (no 1, yes 2)?
 Splitting is particularly recommended in cases
 where long channeling tails are expected.
 2
 Measure of the statistical precision of simulation
 results: ISIGDEPTH?
 20
 Number of amorphous layers on top of
 the single-crystalline substrate (Max.:10):
 0
 Crystalline substrate:
 Temperature different from RT (300K)? (no 1, yes 2)
 1
 Consideration of damage accumulation
 (phenomenological models)? (no 1, yes 2)
 1
 Width of the intervals in the histograms (A)?
 Maximum number of depth intervals is 400
 25
 Final energy in the simulation of
 the motion of the ions?
 Estimation:

E(keV)	Range(A)
0.375E+00	0.657E+01

 Final energy in the simulation of
 the motion of the ions (keV)?
 0.375
 writing to input file s75b.DAT

The input data files s75b.IN and s75b.DAT have been written.

Step 2: Crystal-TRIM simulation using the program xtr041.exe

xtr041.exe < s75b.IN

```

start in981
reading from input file s75b.DAT
input file closed
end in981
start sec971

```

```

end sec971
start pro981
status of calculation in %   particle histories
    10           1000
    20           1999
    30           2998
    40           3997
    50           4996
    60           5995
    70           6994
    80           7993
    90           8992
   100           9991
end pro981
start out981
writing to output file   s75b.OUT
writing to output file   s75b.1D1
output file  s75b.1D1      closed
output file  s75b.OUT      closed
end out981

```

The output data files s75b.OUT, s75b.1D1 and s75b.ST have been written. Only s75b.1D1 is relevant for following postprocessing.

Step 3: Postprocessing using prof1z.exe

prof1z.exe

```

program prof1z
    input data file?
    (not more than 12 ASCII characters)
s75b.1D1
    output data file?
    (not more than 14 ASCII characters)
s75brange.dat
    options:
    iopt
    1      range profile
    2      nuclear energy deposition
    3      electronic energy deposition
    4      damage concentration (only valid in c-Si)
    5      damage probability (only valid in c-Si)
    iopt?
1
    backscattering yield (see file "name.OUT")?
0.
    dose (cm**(-2))?
1.e10
    reading from input file   s75b.1D1
    input file  s75b.1D1      closed
    writing to output file   s75brange.dat
    output file  s75brange.dat  closed

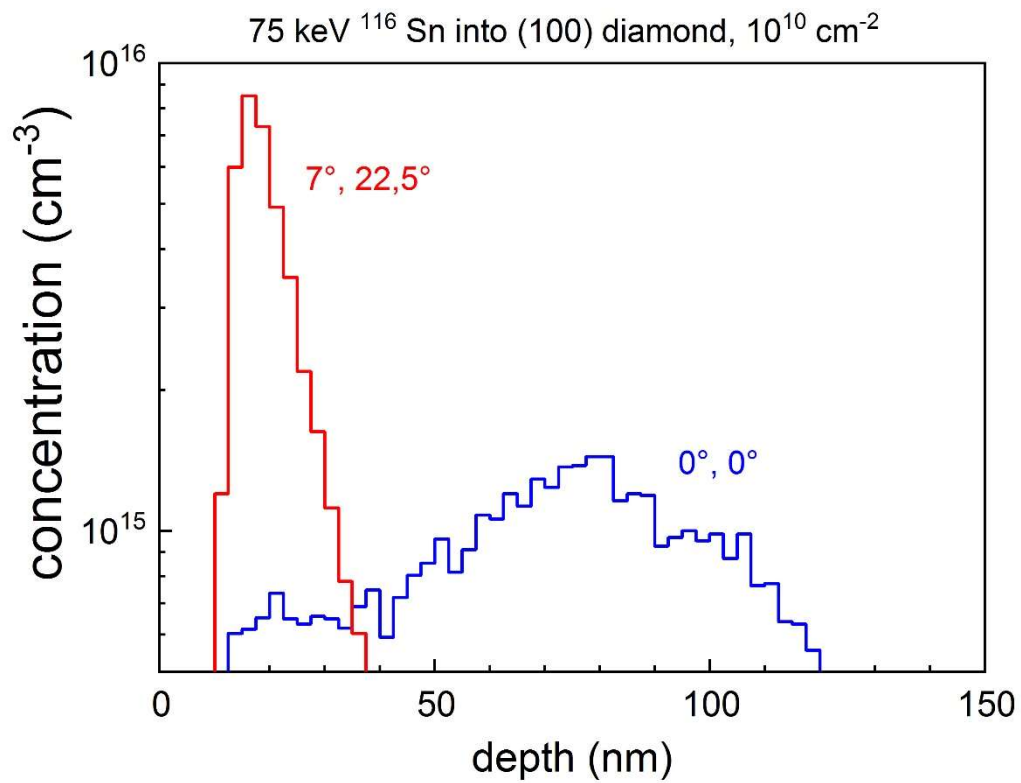
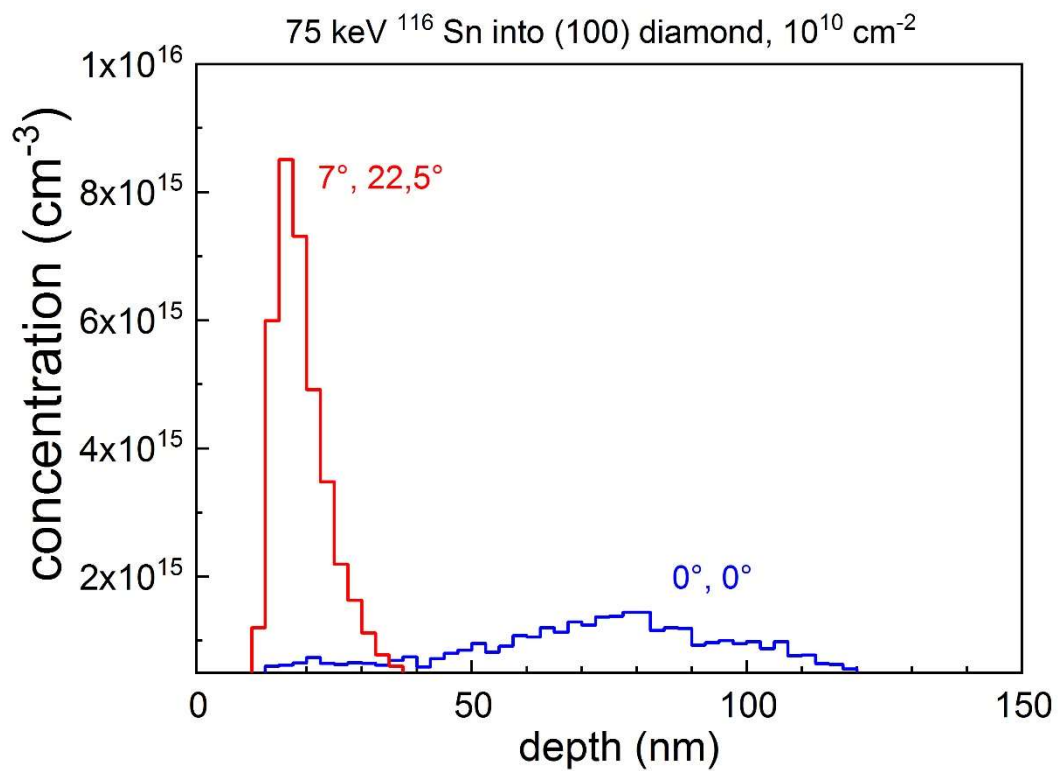
```

Additionally: calculation of the “damage concentration”, i.e. of the concentration of the ballistically displaced atoms (formation of vacancies and self-interstitials):

```
program prof1z
input data file?
(not more than 12 ASCII characters)
s75b.1D1
output data file?
(not more than 14 ASCII characters)
s75bopt4.dat
options:
iopt
1    range profile
2    nuclear energy deposition
3    electronic energy deposition
4    damage concentration (only valid in c-Si)
5    damage probability (only valid in c-Si)
iopt?
4
backscattering yield (see file "name.OUT")?
0.
dose (cm**(-2))?
1.e10
reading from input file    s75b.1D1
input file  s75b.1D1      closed
writing to output file    s75bopt4.dat
output file s75bopt4.dat  closed
```

Graphical representation of P depth profiles for Examples G and H

The following two diagrams show the Sn depth profiles s75arange.dat and s75bdrange.dat, with a logarithmic and a linear concentration scale. The statistics of the histograms can be improved using simulation with more than 10000 projectile histories.



The following diagram shows the concentration of the ballistically displaced atoms.

